

Demand Moore Reliability

Monitoring Clean Room Relative Humidity Levels

Manufacturing of semiconductor wafers requires that clean room temperatures are controlled to very precise temperature and humidity levels. Keeping relative humidity levels in wafer clean rooms below 30% can help prevent the possibility of wafer surface cooling to temperatures below the dewpoint of surrounding air, which can lead to wafer spoilage and out of spec product.

The HART programmable HTZ humidity and temperature transmitter can be trimmed and calibrated to precise levels to ensure the highest wafer production yields. The HTZ comes standard with two separate and isolated 4-20mA signals representing any two of the three variables: temperature, relative humidity or dewpoint.

